

In the United States Patent and Trademark Office

In re Patent Application:

Inventor: Michael D. WELCH et al.

Serial No.: Unknown. (Continuation of SN 09/711,191.)

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Title: Double Slit Valve Doors for Plasma Processing

Prior Examiner: Bueker, R.

Prior Group Art Unit: 1763

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Mail Stop PATENT APPLICATION  
Commissioner for Patents  
P.O. Box 1450  
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**PRELIMINARY AMENDMENT**

Please amend the concurrently filed continuation patent application as follows:

**In the Claims**

Cancel claims 1–30.

Insert the following new claims 31–43:

1 31. A chamber liner apparatus for covering a portion of a cylindrical side wall of a plasma chamber,  
2 comprising:

3 a cylindrical liner having cylindrical inner and outer surfaces;  
4 wherein the liner includes an aperture extending between said inner and outer surfaces;  
5 wherein the outer surface of the liner includes a recess contiguous with the aperture; and  
6 wherein the recess does not extend through the liner to the inner surface of the liner.

1 32. Apparatus according to claim 31, wherein:

2 the aperture and the recess are each characterized by a respective circumferential width  
3 dimension along the circumference of the liner; and  
4 the recess has a circumferential width equal to or greater than the circumferential width of the  
5 aperture.